Features and Benefits
- Maintenance friendly mechanical design
- State of the art modular control system, in-house designed and manufactured
- 10.4” high-res touchscreen for operator interface
- Up to 4 stacked quartz or SiC tube reactor chambers for various processes
- No thermal interference between different tubes
- Contactless fully automated boat-in-tube loading both cantilever or softlanding configurations
- Independent tube level control system
- HW safety interlocks independent on main CPU
- HEPA or ULPA filters installed in load station
- Boat elevator and wafer handling automation
- UHP face seal fittings and welds for connections
- UHP orbital weldings made in 100/10 Cleanroom

Technological Data
- Sample dimensions W x D x H (mm): 5600 x 2600 x 1000
- Wafer size (mm): 150, 200, 300 or any custom size
- Wafer load: 100+
- Heating system: 3 or 5 zone
- Flat zone: Up to 1067 mm (42”)
- Process temperature: 200°C to 1300°C, ± 0.5°C across flat zone
- Power consumption: 18kW - 30kW per tube
- Power supply: (adapted to power grid of destination country)
  - 150 mm: 3-phase, 400 or 480VAC, 140A, 50 or 60Hz
  - 200 mm: 3-phase, 400 or 480VAC, 160A, 50 or 60Hz
- Clean dry air: 70 – 110 psig (4,8 to 7,6 bar)
- Cooling water: 40 – 60 LPM
- Exhaust: 210m³/h per tube
- Options: Boat elevator and wafer handling automation

Processes
- Atmospheric
  - Diffusion (drive-in) high temperature processes
  - Doping from solid, liquid and gaseous dopant sources e.g. BBr₃, B₂H₆, POCl₃, PH₃, BN
  - Various thermal processing e.g. annealing, sintering
  - Pyrogenic wet Oxide with EBS
  - Wet Oxide with ultra pure steamer
  - Dry Oxide
  - HiPOx (High Pressure Oxide)
- LPCVD
  - Silicon nitride
  - Low temperature oxide (LTO)
  - High temperature oxide (HTO)
  - TEOS oxide
  - Polysilicon, with tilt/flat temperature profile
  - Doped polysilicon
  - Oxynitride
- PECVD
  - Silicon nitride (incl. anti-reflective SiN solar cell coating)
  - Silicon oxide
  - Oxynitride
  - DCE or HCl optional for all processes

Full Production
- Horizontal Furnaces
- SVFur-FPx
- SVFur-FFx
- DCE or HCl optional for all processes